



Corporate PR Contact

Dr. Jim Wang
Nanonex Corporation
1-732-355-1600
jwang@nanonex.com

**Nanonex Announces the Shipment and Installation of an Innovative Nanoimprint
Lithography System for Fully Automated Manufacturing**

PRINCETON, NJ, May 19, 2013 – NANONEX CORPORATION, a pioneer and leading company in nanoimprint solutions, today announced the successful delivery and installation of a new nanoimprint lithography (NIL) manufacturing system, the NX-M200B, to a major Japanese manufacturing company.

Nanonex's NX-M200B is a fully-automated, production-ready, advanced nanoimprint lithography tool that has the ability to process a variety of wafer and substrate sizes and types. Based on Nanonex inventions and proprietary technologies, including the Air-Cushion Press™, the NX-M200B offers sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, with ease-of-use, flexibility, and full automation. The flexibility and ease-of-use makes the NX-M200B an ideal tool for manufacturing as well as process development. Besides exceptional fine control of process parameters, it gives the operator broad freedom to monitor and manage imaging, diagnosis, and customized processes in real time.

Nanonex invented nanoimprint lithography (NIL) and pioneered the development of NIL equipment masks, resists, and processes to over 150 customers around the world. "The NX-

M200B represents a new milestone in advanced manufacturing nanoimprint tool development, and provides new capabilities of nanoimprint manufacturing for diverse industrial applications. The flexibility of this tool, to accept multiple wafer sizes and mold materials is an example of the technical expertise of Nanonex to meet customer needs today and in the future. We are very excited about its debut”, said Dr. Linshu Kong, Chief Operating Officer of Nanonex.

About Nanonex Corporation

Nanonex is the inventor of nanoimprint lithography (NIL), the world’s first nanoimprint lithography company, and the world’s leading provider of nanoimprint solutions that include equipment, masks, resists and processes. Nanonex’s patented and proprietary nanoimprint lithography solutions and Air-Cushion Press™ can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of applications, such as optical devices, data storage, displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Nanonex has over 150 customers and an installed base of over 70 tools world-wide. Visit www.nanonex.com for additional information.